

ABSTRACT OF THE DISCLOSURE

To provide an electron exposure apparatus capable of providing high resolution and performing electron exposure at high speed, integrated tips are used, only  
5 the tips provided at ends control distances between the tips and the surface of a wafer and the tips used for electron exposure follow the wafer according to deformations of cantilevers, which occur due to the Coulomb force resultant from a voltage applied to each  
10 tip.

40050314-A01202